

## **SIMULATION WG MEETING 28.4.2015**

### **STATUS AT HELSINKI**

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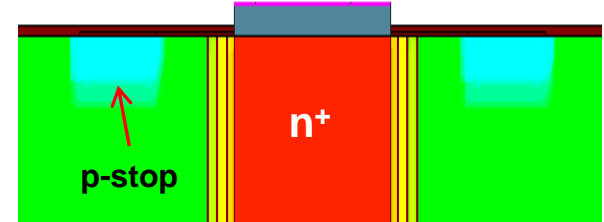
#### **Outline**

- ❑ 3D columnar detector transient & CV/IV simulations:  $\Phi_{eq} = 1e16 \text{ cm}^{-2}$**
- ❑ Phase II pixels: charge sharing at 400 V (simplified structure)**

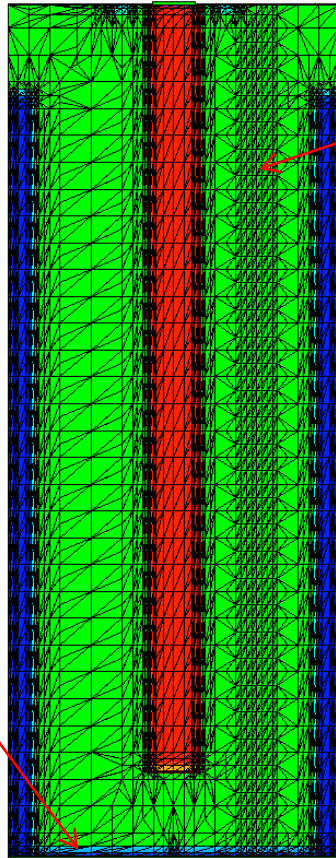
# Double type column 3D-sensor simulations: structure

- ❑ **Double-side double type column 3D-sensor structure**
- ❑ 55x55x200  $\mu\text{m}^3$  structure, 250 nm oxide layer & 500 nm Al on both planes
- ❑ P-type bulk with 180  $\mu\text{m}$   $n^+/p^+$  columns ( $r = 5 \mu\text{m}$ )
- ❑ All  $p^+$  contacts connected together by the backplane Al
- ❑ p-stop depth = 1.5  $\mu\text{m}$ ,  $r_{\text{in}} = 10 \mu\text{m}$ ,  $r_{\text{out}} = 15 \mu\text{m}$

DC-coupled front contact ( $R_{\text{bias}} = 50 \Omega$ )



Diagonal cut

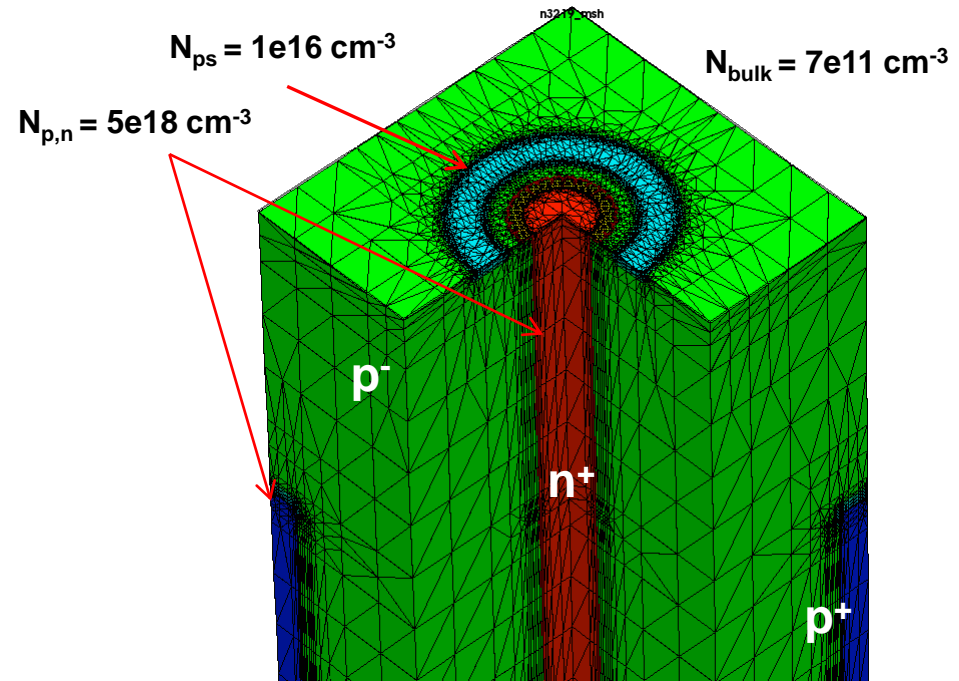


- ❑ Reduced mesh size around MIP trajectory

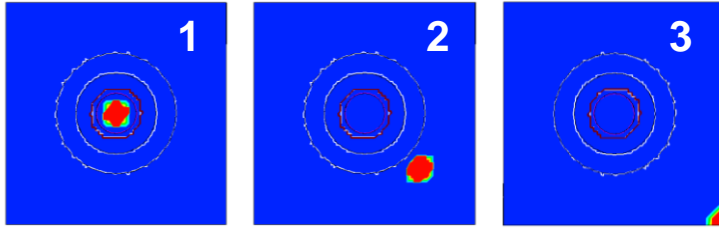
- ❑ 29 615 mesh points (> 30 k: memory allocation crash)
- ❑ Column doping profiles by error function

- ❑  $p^+$  doping at backplane to reduce low field region

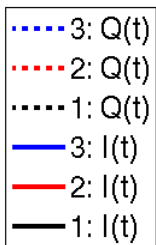
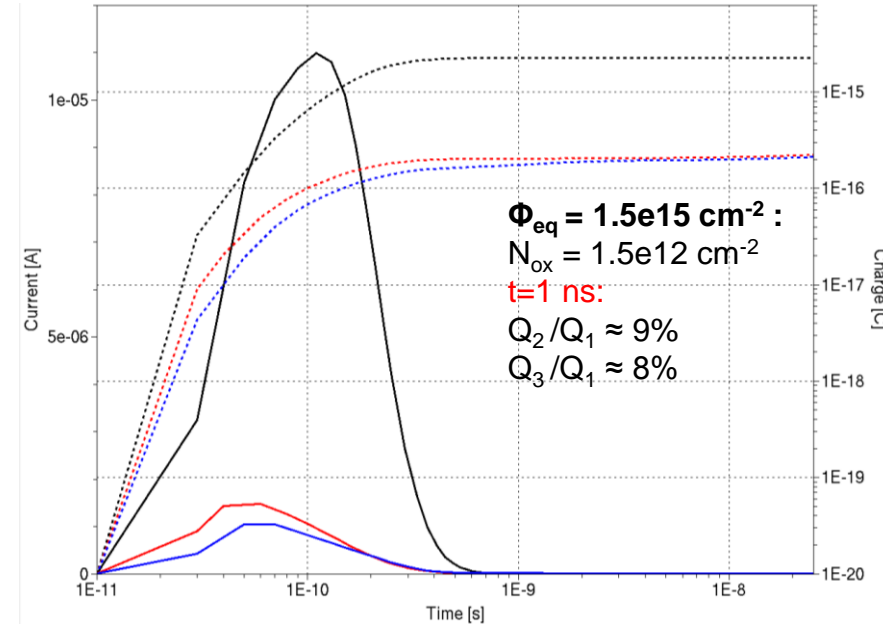
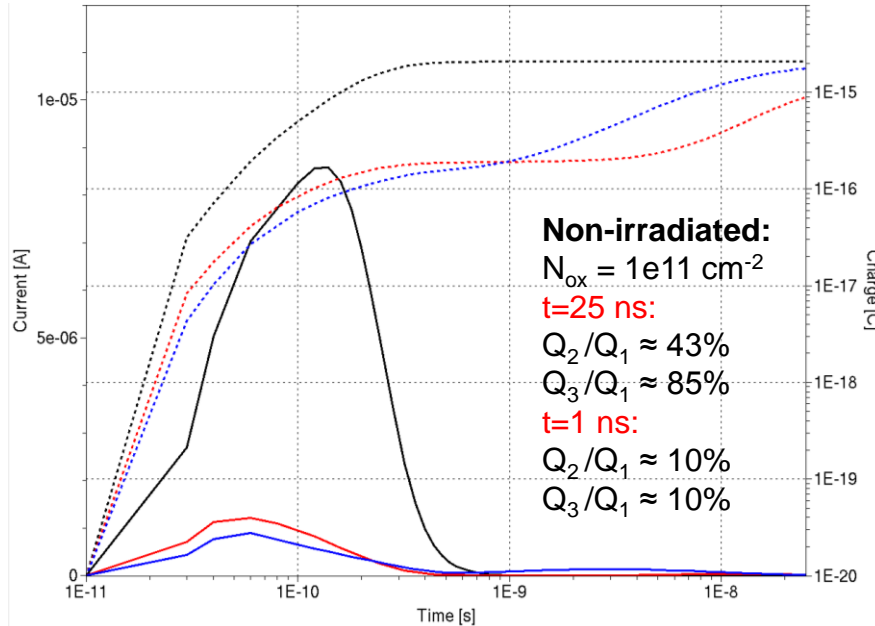
Doping profiles  
(Oxide layer transparent for clarity)



# 3D transient simulations: non-irradiated & protons



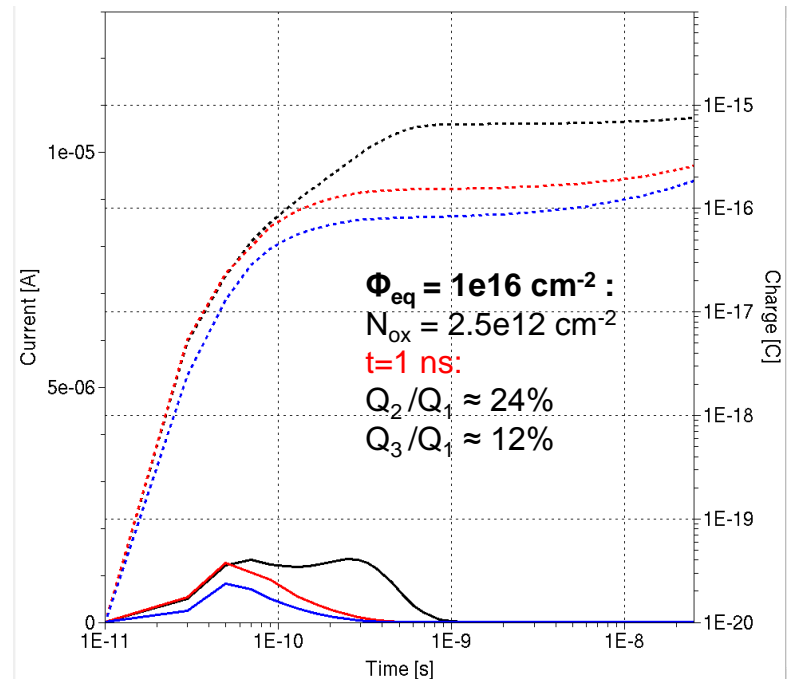
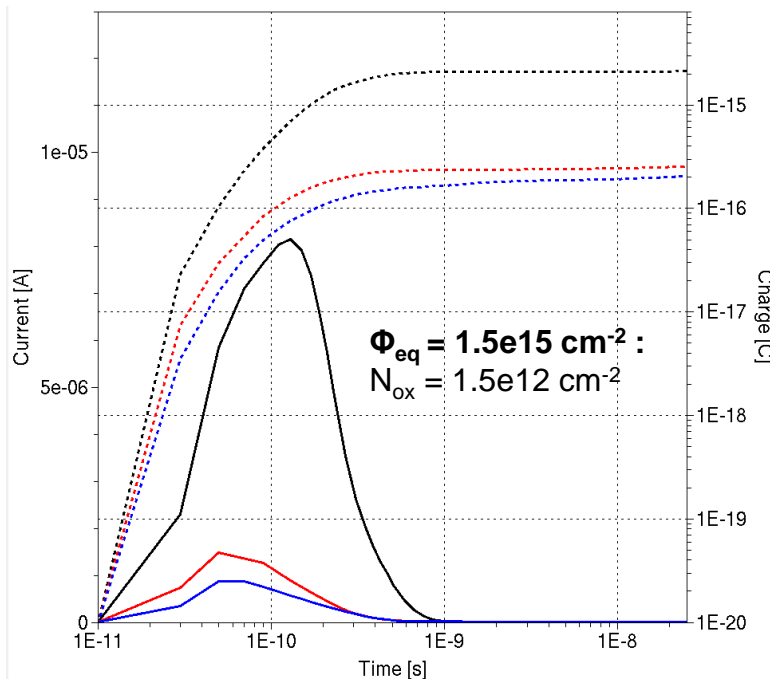
- Hit position 1: n+ column (hole transient)
- Hit position 2: midgap (electron + hole transient)
- Hit position 3: p+ column (electron transient)
- V=-100 V, T=253 K (non-irradiated: T=293 K), MIP  $\sigma = 0.5 \mu\text{m}$
- DC-coupled contacts:  $R_{\text{front}} = R_{\text{back}} = 50 \Omega$



## Defects

- **Bulk:** proton model
- **Within 2  $\mu\text{m}$  of surface:** proton model + shallow acceptors  
= non-uniform 3-level model

# 3D transient simulations: high $\Phi$ @ V=40 V



- .....3: Q(t)
- .....2: Q(t)
- .....1: Q(t)
- 3: I(t)
- 2: I(t)
- 1: I(t)

□ Essentially no voltage dependence between 40 V – 100 V for  $\Phi_{eq} = 1.5e15 \text{ cm}^{-2}$

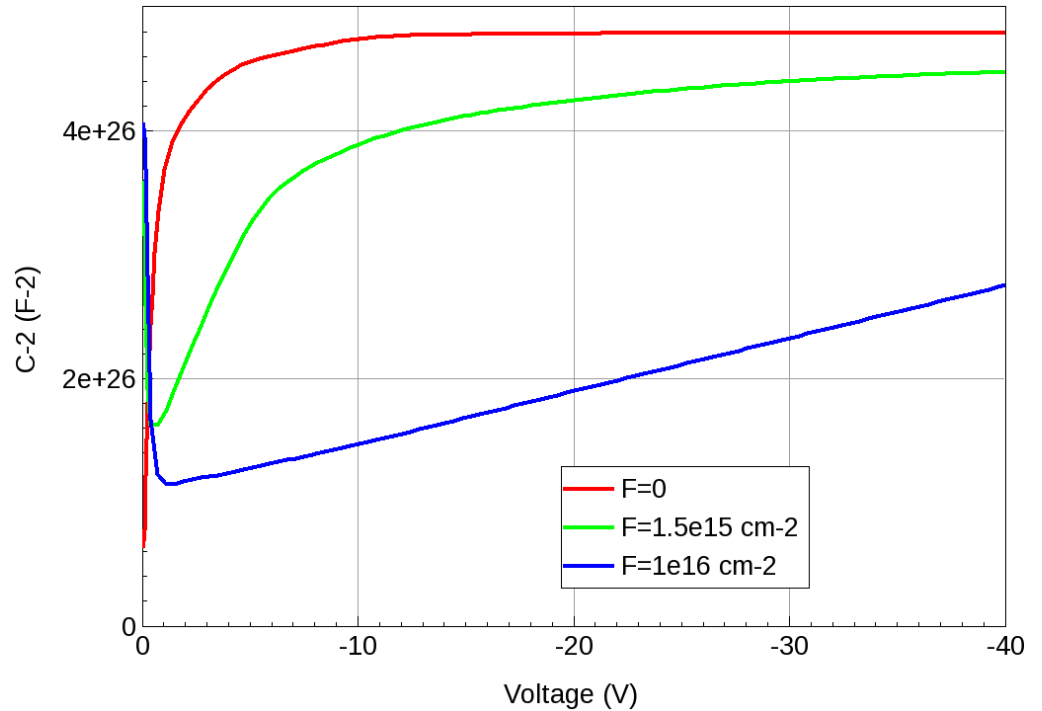
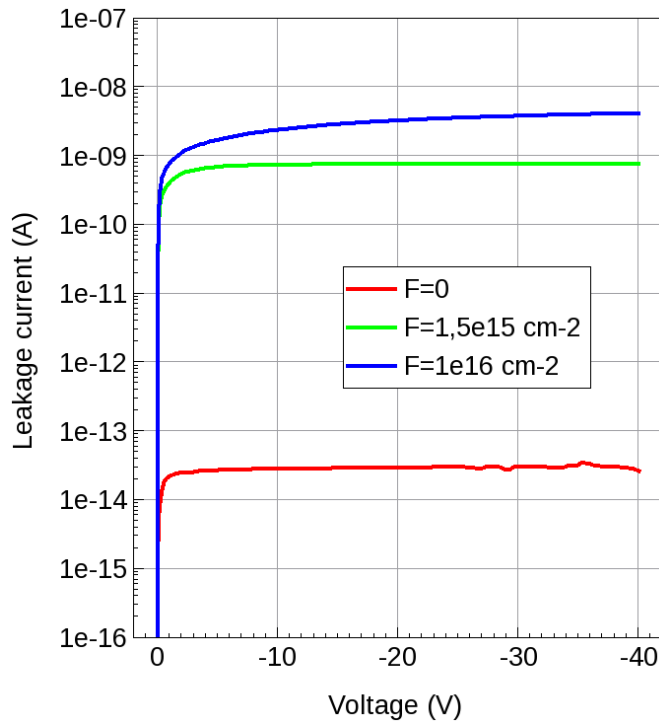
□ **Position 2 (midgap) most radiation hard:**  $\frac{1}{2}$  of max. drift distance between electrodes

□ **Position 1 (n+): Pros:** high E region, **Cons:** transient from holes

□ **Position 3 (p+): Pros:** transient from electrons, **Cons:** low E region

Hit position	Fluence [ $\text{cm}^{-2}$ ]	CCE @ 1 ns [%]
1	1.5e15	100
2	1.5e15	100
3	1.5e15	90
1	1e16	34
2	1e16	85
3	1e16	42

# 3D CV/IV simulations: high $\Phi$ @ V=40 V



$$\alpha (253\text{K}) = 8.9 \cdot 10^{-19} \text{ A} \cdot \text{cm}^{-1}$$

$$I = V \cdot \alpha \cdot \Phi$$

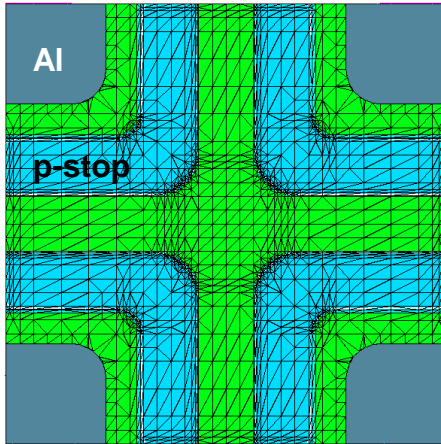
$$\rightarrow I(1.5e15) \approx 0.8 \text{ nA}$$

$$I(1e16) \approx 5.4 \text{ nA}$$

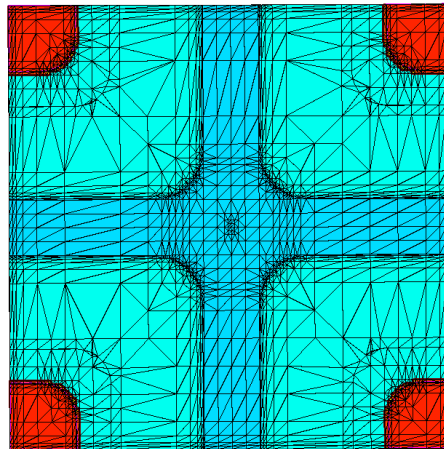
- Irradiated LC agrees with experimental also @  $\Phi_{\text{eq}} = 1e16 \text{ cm}^{-2}$
- $\Phi_{\text{eq}} = 1e16 \text{ cm}^{-2}$ : Sensor not fully depleted @ V=40 V

# Phase II pixel: Corner region structure

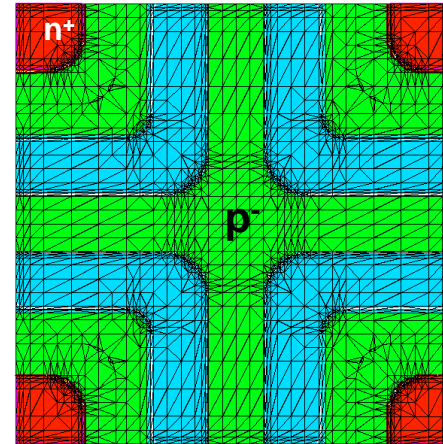
Normal: P-stop with Al



Normal: P-spray & implants



Normal: P-stop & implants

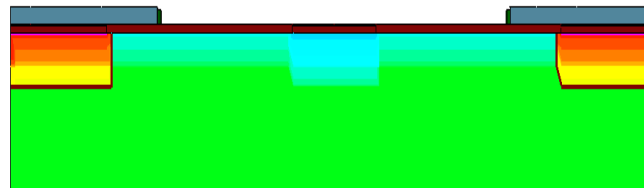


$N_n = 1e19 \text{ cm}^{-3}$

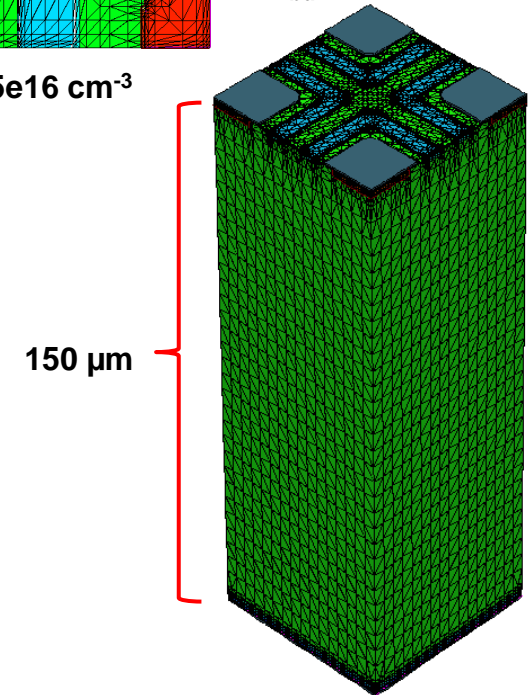
Normal (N):  $23/4 = 5.75$   
Wide (W):  $30/4 = 7.5$

N: 6.0  
W: 5.0  
N: 5.0  
W: 3.0  
N: 5.0  
W: 4.0

$N_{pstop} = 5e16 \text{ cm}^{-3}$



$N_{bulk} = 1.68e12 \text{ cm}^{-3}$



150 μm

- ❑ **Corrected** moderate p-spray:
  - Center: peak= $1e17 \text{ cm}^{-3}$ ,  $d=1.5\mu\text{m}$
  - Elsewhere: peak= $1e15 \text{ cm}^{-3}$ ,  $d=1\mu\text{m}$

- ❑ Normal & wide designs,  $MO = 3 \mu\text{m}$
- ❑ Minimized complexity: 'ideal' DC-coupling (no vias/punch throughs)
- ❑ Mesh points: from ~30k to ~106k
- ❑  $\frac{1}{4}$  of implant included for corner region simulations to maximize mesh density

# Normal vs wide: $V_{bd}$ for p-bulk tuned lifetimes

□ Corrected moderated p-spray design  
(single high concentration region)

□  $Q_f = 1e11 \text{ cm}^{-2}$

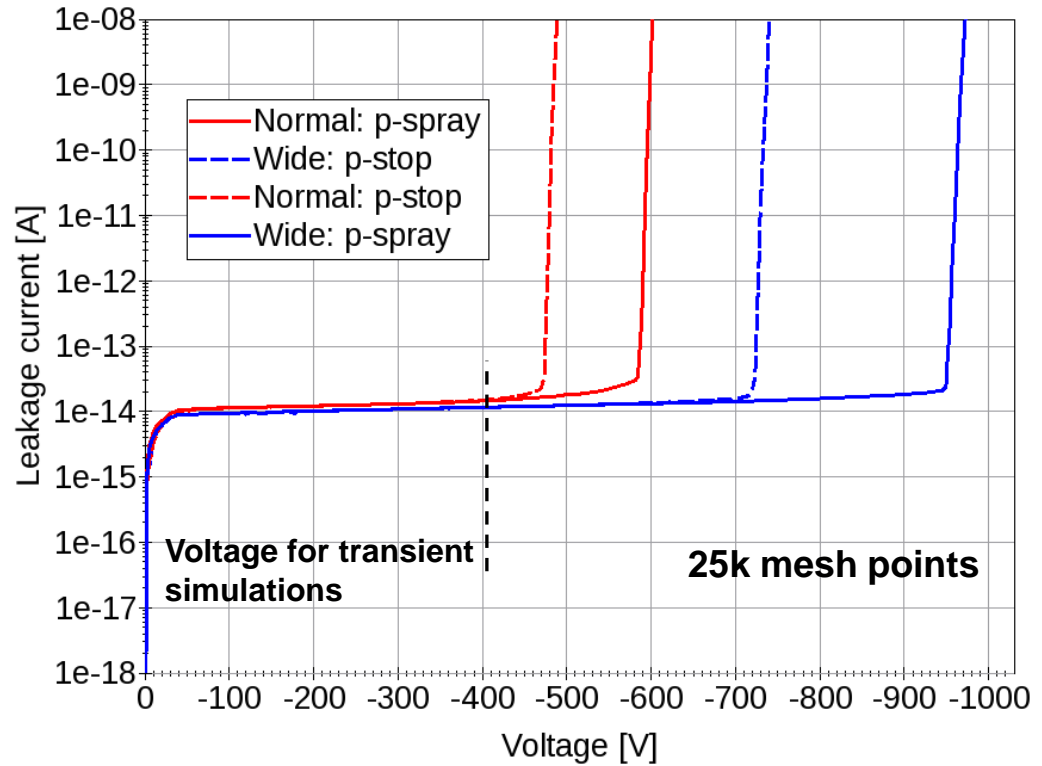
□ Tuned e & h lifetimes for p-bulk:

$\tau_e = 1e-2 \text{ s}$ ,  $\tau_h = 1e-2 \text{ s}$

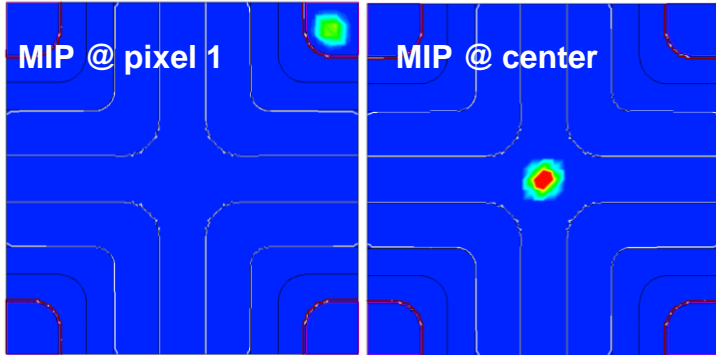
▪ **Normal:**  $V_{bd}(\text{p-spray}) \approx 590 \text{ V}$ ,  $V_{bd}(\text{p-stop}) \approx 470 \text{ V}$

▪ **Wide:**  $V_{bd}(\text{p-spray}) \approx 950 \text{ V}$ ,  $V_{bd}(\text{p-stop}) \approx 720 \text{ V}$

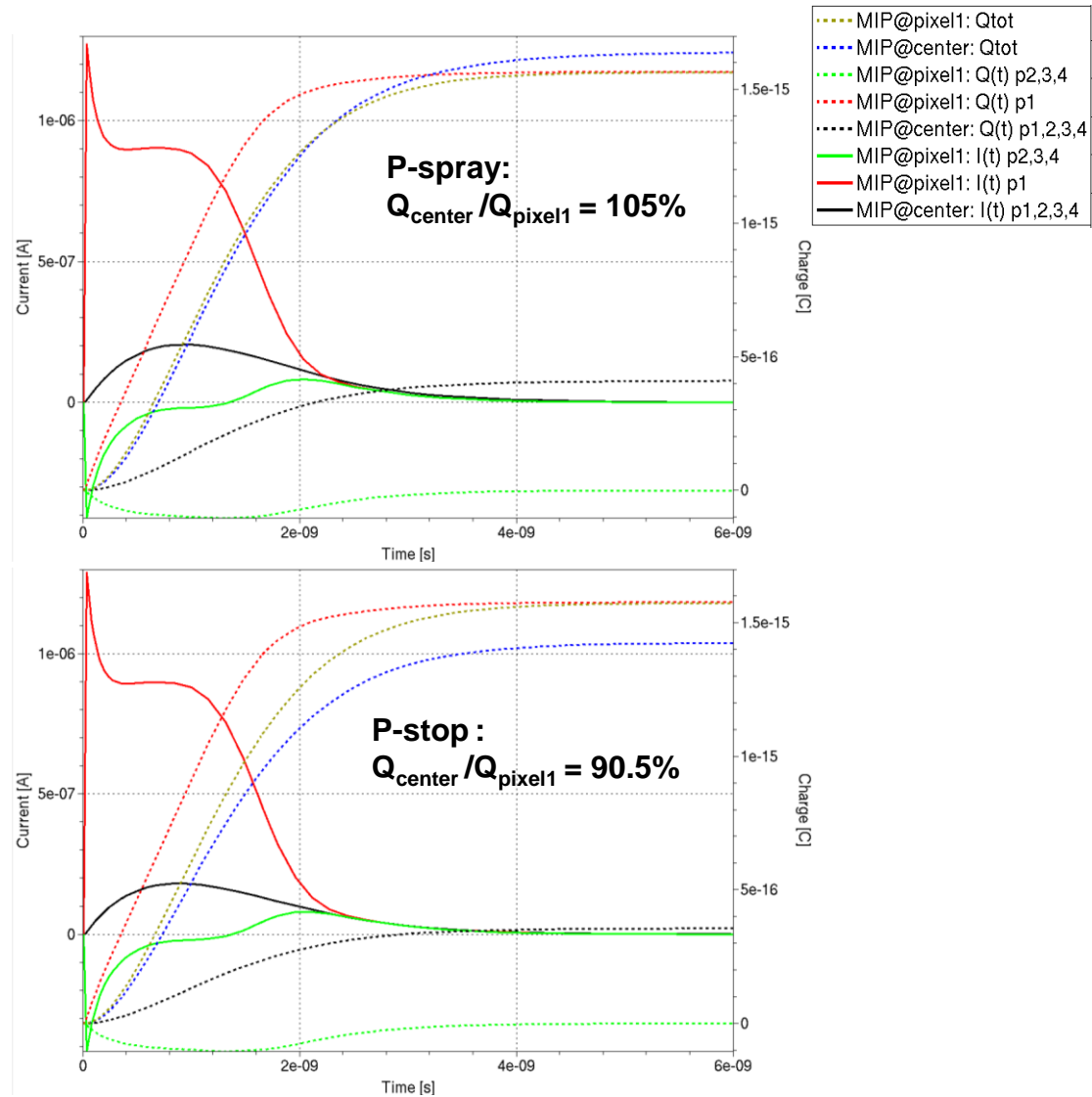
→ **superior  $V_{bd}$  for wide design with p-spray**



# Transient simulations: charge sharing of 'Normal' design



- MIP injection at pixel 1 & center
- Non-irradiated,  $V = -400\text{ V}$ ,  $Q_f = 1e11\text{ cm}^{-2}$ ,  $T = 293\text{ K}$
- MIP @ pixel 1:
  - Charge sharing = 0
- MIP @ center:
  - **P-spray**: higher cluster charge than for MIP @ pixel 1!
  - **Charge loss >10% higher for p-stop** with  $N_{ps} = 5e16\text{ cm}^{-3}$ ,  $d=1.5\text{ }\mu\text{m}$





# Transient simulations: charge sharing of 'Wide' design

- ❑ MIP injection at pixel 1 & center
- ❑ Non-irradiated,  $V = -400$  V,  $Q_f = 1e11$  cm<sup>-2</sup>,  $T = 293$  K
- ❑ MIP @ pixel 1:
  - Equal collected charges between isolation methods
  - Charge sharing = 0
- ❑ MIP @ center:
  - Charge loss 4% higher for p-stop with  $N_{ps} = 5e16$  cm<sup>-3</sup>,  $d=1.5$  μm

## CONCLUSIONS:

- ❑ Normal with p-stop: Lowest  $V_{bd}$ , highest charge loss @ center injection
- ❑ Wide with p-spray: Highest  $V_{bd}$ , 1.3% charge loss @ center injection

